

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	1	10/813799	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:07
L2	3837	(measur\$3 detect\$3 inspect\$3) with (particles defect) and (calculat\$3 determin\$3) with chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:13
L3	15	2 and clean\$3 near mode	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:10
L4	28	2 and film near2 peel\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:10
L5	6	2 and (film near2 peel\$3) near7 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:10
L6	620	((measur\$3 detect\$3 inspect\$3) with (particles defect)) with ((calculat\$3 determin\$3) with chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:14
L7	330	((measur\$3 detect\$3 inspect\$3) with (particles defect)) with ((calculat\$3 determin\$3) near7 chamber)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:14
L8	27	7 and "356"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:14
L9	12	7 and "438"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:15

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L10	35	7 and "250"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:15
L11	6	7 and "156"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:15
L12	2	7 and "216"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:15
L13	63	(((((8 or 9) or 10) or 11) or 12)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:16
L14	14	13 and compar\$3 with (threshold predetermin\$3 reference standard)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/08/15 10:16

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L1	2	(situ and monitor\$3 and particles and react\$3 and film near peel\$3 and interior and wall and chamber and semiconductor and condition clean\$3 and mode and excit\$3 and intensity and threshold and compar\$3).clm.	US-PGPUB; USPAT	OR	ON	2007/08/15 10:23
L2	0	(situ and monitor\$3 and particles and react\$3 and film near peel\$3 and interior and wall and chamber and semiconductor and condition and clean\$3 and mode and excit\$3 and intensity and threshold and compar\$3).clm.	US-PGPUB; USPAT	OR	ON	2007/08/15 10:22
L3	1	(situ and monitor\$3 and particles and react\$3 and film near peel\$3 and interior and wall and chamber and semiconductor and condition and excit\$3 and intensity and threshold and compar\$3).clm.	US-PGPUB; USPAT	OR	ON	2007/08/15 10:22